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(71) Applicant (for all designated States except US): FUJIFILM Corporation [JP/JP]; 26-30, Nishiazabu 2-chome, Minato-ku, Tokyo, 1068620 (JP).

(72) Inventors; and

(75) Inventors/Applicants (for US only): ENOMOTO, Yuichiro [JP/JP]. TARUTANI, Shinji [JP/JP]. SHIBUYA, Akinori [JP/JP]. YAMAGUCHI, Shuhei [JP/JP].

(74) Agents: SUZUYE, Takehiko et al.; c/o SUZUYE & SUZUYE, 1-12-9, Toranomon, Minato-ku, Tokyo, 1050001 (JP).

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(54) Title: METHOD OF FORMING PATTERN USING ACTINIC-RAY- OR RADIATION-SENSITIVE RESIN COMPOSITION, AND PATTERN

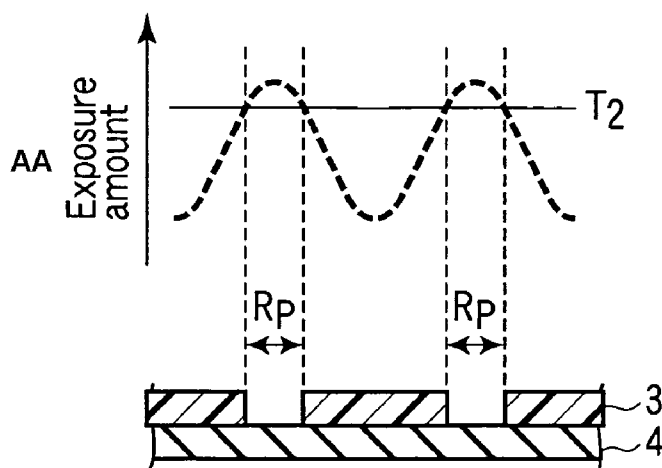


FIG. 1A

(57) Abstract: According to one embodiment, a method of forming a pattern includes the step of applying an actinic-ray- or radiation-sensitive resin composition on a substrate so as to form a film, the step of selectively exposing the film through a mask and the step of developing the exposed film with the use of a developer containing an organic solvent, wherein the actinic-ray- or radiation-sensitive resin composition contains a resin (A) whose polarity is increased by the action of an acid so that the solubility of the resin in the developer containing an organic solvent is decreased, a photoacid generator (B) that when exposed to actinic rays or radiation, generates an acid containing a fluorine atom and a solvent (C), and wherein the photoacid generator (B) is contained in the composition in a ratio of 8 to 20 mass% based on the total solids of the composition.